

MNC 2016



November 8th(TUE.)-11th(FRI.), 2016
ANA Crowne Plaza Kyoto, Kyoto, Japan

PLENARY SPEAKER

Design Technology CoOptimization, the Key to Unlocking New Scaling Pathways

Lars Liebmann, GLOBALFOUNDRIES, USA

Theme: Organic Display, Printed Electronics, Stretchable Electronics

Sang Yoon Lee, Samsung Advanced Inst. of Technol., Korea

Theme: 2D Materials

Kaustav Banerjee, UCSB, USA

CONFERENCE SCOPE

1: Lithography and Related Technologies and Metrology

1-1: Advanced Photolithography

1-2: Electron and Ion Beam Technologies

1-3: Resist and Directed Self-Assembly

2: Nanotechnology

2-1: Nanocarbons

2-2: Nanodevices

2-3: Nanofabrication

2-4: Inorganic Nanomaterials

2-5: Organic Nanomaterials

2-6: NanoTool

3: Nanoimprint, Nanoprint and Rising Lithography

4: BioMEMS, Lab on a Chip

5: Microsystem Technology and MEMS

ABSTRACT DEADLINE

July 1st, 2016

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